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IAP11 Rec'd PCT/PTO 03 AUG 2006**INFORMATION DISCLOSURE
STATEMENT (PTO 1449)**ATTORNEY DOCKET NO.
70020.0079USWOU.S. APPLICATION SERIAL NO.
To Be Assigned CONFIRMATION NO
N/ABASED ON INTERNATIONAL APPLICATION NO.
PCT/JP2005/009128INTERNATIONAL FILING DATE
May 19, 2005

INVENTOR(S)	EXAMINER	GROUP ART UNIT
Takashi MIYAMATSU, et al.	Not Assigned	N/A

TITLE OF APPLICATION

LIQUID FOR IMMERSION EXPOSURE AND IMMERSION EXPOSURE METHOD**U.S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
A	5,817,256	10/06/1998	WEIPPERT			
B	US 2002/0006675 A1	01/17/2002	SHIGARAKI			
C	US 2004/0242825 A1	12/02/2004	SHISHIDO ET AL.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
D	JP 11-176727	07/02/1999	JAPAN			Abstract
E	JP 10-303114	11/13/1998	JAPAN			Abstract
F	JP 2003-160515	06/03/2003	JAPAN			Abstract
G	JP 2001-181217	07/03/2001	JAPAN			Abstract
H	JP 60-209536	10/22/1985	JAPAN			Abstract
I	JP 2004-123762	04/22/2004	JAPAN			Abstract
J	JP 2002-255866	09/11/2002	JAPAN			Abstract
K	JP 06-12452	02/16/1994	JAPAN			X
L	JP 09-241214	09/16/1997	JAPAN			Abstract
M	JP 07-220990	08/18/1995	JAPAN			Abstract
N	JP 2001-326162	11/22/2001	JAPAN			Abstract
O	WO99/49504	09/30/1999	WIPO			Abstract
P	AU 2747999	10/18/1999	AUSTRALIA			Abstract
Q	WO03/016365	02/27/2003	WIPO			Abstract
R	WO01/032739	05/10/2001	WIPO			Abstract
S	JP 62-094813	05/01/1987	JAPAN			Abstract

EXAMINER	DATE CONSIDERED
/Peter Kim/	03/16/2009

EXAMINER: Initial if the reference is considered, whether or not the citation is in conformance with MPEP 609. Draw a line through the citation if it is not in conformance and it is not considered. Include a copy of this form with the next communication to the Applicant.

INFORMATION DISCLOSURE STATEMENT (PTO 1449)		ATTORNEY DOCKET NO. 70020.0079USWO	CONF. NO. N/A
		U.S. APPLICATION SERIAL NO. To Be Assigned	BASED ON INTERNATIONAL APPLICATION NO. PCT/JP2005/009128
INVENTOR(S) Takashi MIYAMATSU, et al.		EXAMINER (If known) Not Assigned	INTERNATIONAL FILING DATE May 19, 2005
			ART UNIT (If known) N/A

FOREIGN PATENT DOCUMENTS								
	T	JP 2001-068400	03/16/2001	JAPAN			Abstract	
	U	JP 11-233402	08/27/1999	JAPAN			Abstract	
	V	JP 2005-072230	03/17/2005	JAPAN			Abstract	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
W	Inside Memory, Nikkei Microdevice, p. 77-86 (April 2004).
X	Smith, et al., Approaching the numerical aperture of water-Immersion lithography at 193nm, Proc. SPIE, Vol. 5377, pp. 273-284 (2004).
Y	Sylvester-Hvid, et al., Refractive Indices of Molecules in Vapor and Liquid: Calculations on Benzene, J. Phys. Chem. A, Vol. 103, No. 42, pp. 8447-8457 (1999).
Z	Immersion Lithography Modeling 2003 year-End Report (International SEMATECH).
AA	The seminar text of special seminar on immersion exposure technology, pp. 14-33 (May 27, 2004).

EXAMINER <i>/Peter Kim/</i>	DATE CONSIDERED 03/16/2009
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